



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

1752  
Rhu

In re application of

: **MAIL STOP AMENDMENT**

Satoshi MAEMORI et al.

: **Confirmation No. 9635**

Serial No. 09/955,111

: Docket No. 2001-1300A

Filed September 19, 2001

: Group Art Unit 1752

POSITIVE-WORKING PHOTORESIST  
COMPOSITION AND PHOTSENSITIVE  
MATERIAL USING SAME

: Examiner S. LEE

**RESPONSE**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In response to the Official Action dated April 21, 2004, the period for response having been extended for two months by the attached petition, please amend the present application as follows: